

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

PUBLICATION NUMBER : 04196117

PUBLICATION DATE : 15-07-92

APPLICATION DATE : 26-11-90

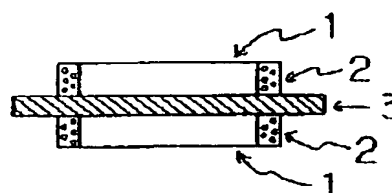
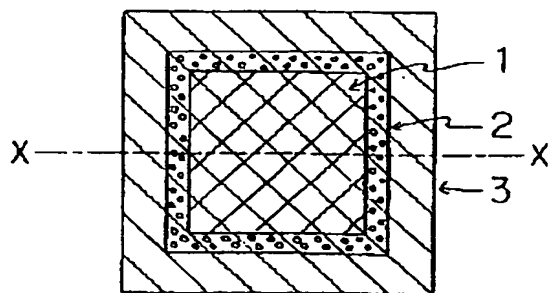
APPLICATION NUMBER : 02321762

APPLICANT : SEIKO EPSON CORP;

INVENTOR : YASUHARA MASANORI;

INT.CL. : H01L 21/027 G03F 1/14

TITLE : SEMICONDUCTOR MANUFACTURING  
DEVICE



**ABSTRACT :** PURPOSE: To maintain pellicle in flat condition at all times and decrease the inferiority in development by foreign matter by removing the atmospheric pressure difference between the inside of the pellicle and the outside air at all times, using a porous material for a pellicle frame.

CONSTITUTION: Pellicle frames 2 constituted of frame-shaped porous materials are bonded to the surface and the rear of a glass mask 3, and further pellicles 1 are bonded to the frames 2. Accordingly, if the frames 2 is used to support the pellicles 1 to protect the mask 3, a ventilation port becomes needless, and also a dust-free tape, which is usually stopping the ventilation port, becomes needless, so the structure becomes simple, and the manufacturing also becomes easy. And by the frames 2 always enabling the ventilation between the inside of the pellicle and the outside air, the distortion of pellicle 1 can be prevented, and also the pellicle 1 can always maintain its flat condition. Accordingly, the distortion of the photopattern by the distortion of the pellicle 1 and the inferiority in detection of the foreign matter on the pellicle 1 go, and quality and yield can be improved.

COPYRIGHT: (C)1992,JPO&Japio